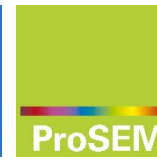




Software solutions for
optimizing micro & nano
fabrication processes



EIPBN BEAMeeting

BEAMeeting San Francisco 2023 Technical Workshop & Discussion



Time: Tuesday, May 30th, 2023 9:00 am – 3:00 pm

Location: Hilton San Francisco Union Square, 333 O'Farrell Street, San Francisco, California 94102, USA

Room : Continental Ballroom 3, Tower 3, Ballroom Level

BEAMeetings are a technical exchange platform for the direct write community focused on e-Beam and laser lithography, data-preparation, PEC, process correction, lithography simulation, and metrology. It is a platform for BEAMER users and those who are interested in GenISys software.

As in the past, it is a great opportunity to meet with the GenISys team, have face-to-face in-depth discussions, exchange ideas and position your needs and wishes. In addition to BEAMER/TRACER, this year we would like to emphasize ProSEM, our full metrology solution for your nanofabrication center.

Please save the date in your calendar and register our BEAMeeting:

On-Site in San Francisco – [REGISTER here](#)

Online via TEAMS – [REGISTER here](#)

or visit our Homepage for the details: [EIPBN BEAMeeting 2023](#).

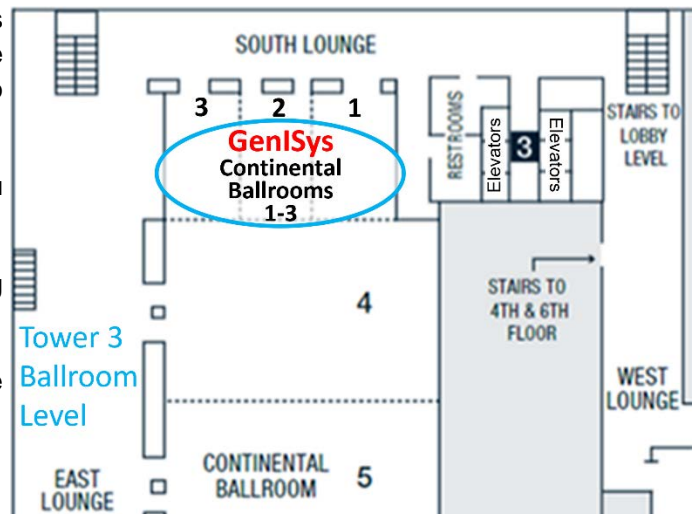
The BEAMeeting is free of charge, lunch and coffee/drinks along with a light breakfast included. Please feel free to share this information with interested colleagues who may wish to join the BEAMeeting.

Please contact us (marketing@genisys-gmbh.com) if you have any questions or any suggestions.

We are looking forward to presenting you with an interesting and valuable workshop!

Please visit our booth #110 on the exhibition floor in the Golden Gate Ballroom, Tower 3, Lobby Level, Tues-Thurs.

Thank you,
The GenISys Team





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BEAMeeting E-Beam & Laser Workshop Technical Workshop & Discussion

Date: Tuesday, May 30th, 2023 - Time: 09:00 – 3:00 pm
Hilton S.F. Union Square – Continental Ballroom 3, Ballroom Level/Floor

Agenda

	Light Breakfast	8:30 am
Ulrich Hofmann GenISys	Welcome & Introduction GenISys Update	9:00 am
Niels Wijnaendts van Resandt LAB14	LAB14 Group Introduction and Overview	9:20
Anja Voigt Micro Resist Technology GmbH	Update on Cross-Functional Photoresists and Photopolymers	9:30
Marvin Zai GenISys	PEC in a FLASH	9:50
Chad Eichfeld Penn State Univ.	ProSEM and TRACER Process Calibration to Achieve Cross Wafer sub-10 nm CD-variation	10:10
	Coffee Break	10:30
Scott Lewis Sci-Tron Limited	Advantages of Metal Organic Resists	10:50
Mark Mondol MIT	Fabricating Flat Lenses by Refractive Index Modification with Ebeam Patterning	11:10
Marvin Zai GenISys	Data Preparation for High Density Gratings	11:30
Fabien Grisé Penn State Univ.	Behind the Curve - How to Pattern Curved Substrates Using EBL	11:50
	Lunch	12:10 pm
Alexei Bogdanov ALB Consulting	Characterization of Beam Shape, Placement Accuracy, and Overlay in E-beam Lithography using 2-D Vernier Arrays	1:00
Justin Worth Purdue	LayoutPy Honeycombs: Simplifying a Painful Pattern	1:20
Kaustubh Vyas GenISys	Beyond the Limits of the Microcosm: Mastering Data Preparation and Virtual Fabrication Strategies for Sub-100 nm Structures	1:40
	Coffee Break	2:00
Sven Bauerdick GenISys	ProSEM: What's new and feedback	2:20
Thomas Michels GenISys	What's New in BEAMER and Roadmap Discussion	2:30
	FINAL Closing	3:00

Agenda is subject to change

